

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: <b>Davis, et al.</b>	§	Case: <b>AMAT/7938/ETCH/SILICON/JB</b>
	§	
Serial No.: <b>10/628,001</b>	§	Filed: <b>July 25, 2003</b>
	§	
Examiner: <b>Stevenson, Andre C.</b>	§	Group Art Unit: <b>2812</b>
	§	
Confirmation No.: <b>3943</b>	§	
	§	
Title: <b>METHOD FOR AUTOMATIC</b>	§	
<b>DETERMINATION OF</b>	§	
<b>SEMICONDUCTOR PLASMA</b>	§	
<b>CHAMBER MATCHING AND</b>	§	
<b>SOURCE OF FAULT BY</b>	§	
<b>COMPREHENSIVE PLASMA</b>	§	
<b>MONITORING</b>	§	

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 Commissioner for Patents  
 P.O. Box 1450  
 Alexandria, VA 22313-1450

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**RESPONSE TO FINAL OFFICE ACTION DATED FEBRUARY 10, 2006**

In response to the Final Office Action dated February 10, 2006, having a shortened statutory period for response set to expire on May 10, 2006, please enter this response and reconsider the claims pending in the application for reasons discussed below. Although Applicants believe that no fee is due in connection with this response, the Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782 for any fees, including extension of time fees or excess claim fees, required to make this response timely and acceptable to the Office.